			1 55	Time stamp
L	Hits	Search Text	DB ,	Time scamp
Number		· .		0004/02/11
1	66	438/288.ccls.	USPAT	2004/03/11
	i			10:47
2	906	438/585.ccls. 438/591.ccls.	USPAT	2004/03/11
1				10:47
3	963	(438/585.ccls. 438/591.ccls.)	USPAT	2004/03/11
200000	-	438/288.ccls.	1	10:47
		**************************************	1	1 14.01
	20394	gate adj2 insulating	USPAT;	2002/10/29
	2000	9400 449 4444	EPO; JPO	16:07
l _	19039	thin adj2 oxide) (ultrathin adj2 oxide	USPAT;	2002/10/29
-	15055	l	EPO; JPO	16:07
_	1124	(gate adj2 insulating) and (thin adj2	USPAT;	2002/10/29
_	1124	oxide) (ultrathin adj2 oxide) and	EPO; JPO	16:08
		polysilicon	1210, 010	1 - 3
	100100		USPAT;	2002/10/29
-	188199	hydrogen and oxygen	EPO; JPO	16:08
1		())	USPAT;	2002/10/29
-	227	(hydrogen and oxygen) and ((gate adj2	EPO; JPO	16:08
		insulating) and (thin adj2 oxide)	EPO; JPO	10.00
		(ultrathin adj2 oxide) and polysilicon)		2002/10/29
-	101606	hydrogen same oxygen	USPAT;	
			EPO; JPO	16:09
-	122		USPAT;	2002/10/29
		insulating) and (thin adj2 oxide)	EPO; JPO	16:13
	İ	(ultrathin adj2 oxide) and polysilicon)		
-	80371	hydrogen with oxygen	USPAT;	2002/10/29
			EPO; JPO	16:14
_	88	(hydrogen with oxygen) and ((gate adj2	USPAT;	2002/10/30
		insulating) and (thin adj2 oxide)	EPO; JPO	10:11
		(ultrathin adj2 oxide) and polysilicon)		
_	1		USPAT;	2002/10/30
	_	insulating) and (thin adj2 oxide)	EPO; JPO	10:16
		(ultrathin adj2 oxide) and polysilicon)		
		and ISSG		
_	9		USPAT;	2004/02/26
1		1000 all product gollowers.	EPO; JPO	13:44
1_	8	(ISSG "in situ steam generation") and	USPAT;	2002/10/30
-	°	qate	EPO; JPO	10:31
L	<u> </u>	gace	1220, 020	1

Search History 3/11/04 10:48:00 AM Page 1

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S4			Landon 1	TTG D D M	T 2002 /04 /07
S4	-	5957	EEPROM and oxide	USPAT;	2003/04/27
280 EEPROM and ("form oxide")		E 4	(FERROM and swide) and CONOC		
- 280 EEPROM and ("form oxide") USPAT; 2003/04/27 EEPG, JPO 14:52 14:53 14:5	-	34	(LEPROM and Oxide) and Sonos		
Comparison of the property o	l _	280	EEPROM and ("form oxide")		
Deprecation of the content of the	1	200	BETROIT and (FOTM OXIGE)		
adj3 hydrogen)	-	0	EEPROM and ("form oxide") near (oxygen		
-	!	•	, , , ,		
hydrogen 14:53 14:54 ("wet oxidation" or "steam oxidation") LEPG; JPO 14:53 2003/04/27 2003/04/28 2003/0	_	1		USPAT;	2003/04/27
and EEPROM (("wet oxidation" or "steam oxidation") and EEPROM) and (ultrathin "ultra thin"			hydrogen)	EPO; JPO	14:53
16	-	184	("wet oxidation" or "steam oxidation")	USPAT;	2003/04/27
and EEPROM) and (ultrathin "ultra thin" "ultra-thin") ((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenically soldises) oxidation anneals4 RTO nearl2 (Sin("Si.sub.3" adj "N.sub.4") Si3N4 nitride) (((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) nearl2 (oxidiz93 oxidises) oxidation anneals4 RTO nearl2 (Sin("Si.sub.3" adj "N.sub.4") Si3N4 nitride) (((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) nearl2 (oxidiz93 oxidis93 oxidation anneals4 RTO) nearl2 (Sin("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and "ultrathin oxide" (((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) nearl2 (oxidiz93 oxidis93 oxidation anneals4 RTO) nearl2 (Sin("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near3 oxide) (((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) nearl2 (oxidiz93 oxidis93 oxidation anneals4 RTO) nearl2 (Sin("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and gradner.inv. reoxidize near6 nitrogen ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) nearl2 (oxidiz93 oxidis93 oxidation anneals4 RTO) nearl2 (Sin("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM nearl2 (Oxidiz93 oxidis93 oxidation anneals4 RTO) nearl2 (Sin("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM "N.sub.4") Si3N4 nitride) and EEPROM (RTO "rapid thermal oxidation") near5 minute (SpAT; 2003/04/28 EPO; JPO EPO;					
"ultra-thin"	-	16			
1694				EPO; JPO	15:01
(oxygen or "0.sub.2") or (pyrogenic pyrogenically pyrogenical wet steam)) nearl2 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) nearl2 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)			"ultra-thin")		0000 (04 (00
pyrogenically pyrogenical wet steam) near12 (oxidiz\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride) ((((hydrogen or "H.Sub.2") near "3" (oxygen or "0.sub.2")) or (pyrogenic pyrogenically pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and "ultrathin oxide" ((((hydrogen or "H.Sub.2") near "3" (oxygen or "0.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near3 oxide) (((((hydrogen or "H.Sub.2") near "3" (oxygen or "0.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (siN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (siN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (siN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (siN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (siN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near12 (oxidiz\$3 oxidis\$3 oxidation ultrathin near2 ultrathin near3 ultrathin near3	-	1694			' '
near12 (oxidiz\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N. sub.4") Si3N4 nitride)			(oxygen or "O.sub.2")) or (pyrogenic	EPO; JPO	12:36
anneal\$4 RTO) near12 (SiN("Si.sub.3" adj					
- 0 ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenically exteam)) nearl2 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) nearl2 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and "ultrathin oxide" ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) nearl2 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) nearl2 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near3 oxide) (((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) nearl2 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) nearl2 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) nearl2 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and gardner.inv. - 23 reoxidize near6 nitrogen ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) nearl2 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) nearl2 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and gardner.inv. - 29 ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) nearl2 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) nearl2 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM (RTO "rapid thermal oxidation") near5 minute (RTO "rapid thermal oxidation") near5 minute (RTO "rapid thermal oxidation") near5 minute (SIN("Si.sub.3") adj "N.sub.4") Si3N4 nitride)) and EEPROM (RTO "rapid thermal oxidation") near5 minute (SIN("Si.sub.3") adj "N.sub.4") Si3N4 nitride)) and EEPROM (RTO "rapid thermal oxidation") near5 minute (SIN("Si.sub.3") adj "N.sub.4") Si3N4 nitride)) and EEPROM (RTO "rapid thermal oxidation") near5 minute (SIN("Si.sub.3") adj "N.sub.4") Si3N4 nitride)) and EEPROM (RTO "rapid thermal oxidation") near5 minute (SIN("Si.sub.3") adj "N.sub.4") Si3N4 nitride)) and EEPROM (SIN("Si.sub.3") adj "N.sub.4") Si3N4 nitride)) and EEPROM (SIN("Si.sub.3") adj "N.sub.4") Si3N4 nitride))					
-			, , , , , , , , , , , , , , , , , , , ,		
(oxygen or "0.sub.2")) or (pyrogenic pyrogenically pyrogenicall wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and "ultrathin oxide" ((((hydrogen or "H.Sub.2") near "3" (oxygen or "0.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near3 oxide) ((((hydrogen or "H.Sub.2") near "3" (oxygen or "0.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and gardner.inv. reoxidize near6 nitrogen	- '	0		USPAT;	2003/04/28
near12 (oxidiz\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and "ultrathin oxide" ((((hydrogen or "H.Sub.2") near "3" (oxygen or "0.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near3 oxide) ((((hydrogen or "H.Sub.2") near "3" (oxygen or "0.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and uspAT; EPO; JPO 12:55 uspAT; 2003/04/28 EPO; JPO 12:56 uspAT; 2003/04/28 EPO; JPO 12:56 uspAT; 2003/04/28 EPO; JPO 12:56 uspAT; 2003/04/28 EPO; JPO 13:28 uspAT; 2003/04/28 EPO; JPO uspAT;				EPO; JPO	12:37
anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N. sub.4") Si3N4 nitride)) and "ultrathin oxide" ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N. sub.4") Si3N4 nitride)) and (ultrathin near3 oxide) ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N. sub.4") Si3N4 nitride)) and gardner.inv. reoxidize near6 nitrogen					
"N. sub. 4") Si3N4 nitride)) and "ultrathin oxide" (((((hydrogen or "H. Sub.2") near "3" (oxygen or "0. sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N. sub.4") Si3N4 nitride)) and (ultrathin near3 oxide) - 26 ((((hydrogen or "H. Sub.2") near "3" (oxygen or "0. sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N. sub.4") Si3N4 nitride)) and gardner.inv. - 23 reoxidize near6 nitrogen - 99 ((((hydrogen or "H. Sub.2") near "3" (oxygen or "0. sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (siN("Si.sub.3" adj (oxygen or "0. sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (siN("Si.sub.3" adj "N. sub.4") Si3N4 nitride)) and EEPROM (RTO "rapid thermal oxidation") near5 minute - 2 (RTO "rapid thermal oxidation") near5 minute - 2 (tunnel oxide".clm. "USPAT; 2003/04/28 EPO; JPO 13:28 2004/02/26					
Oxide" ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near3 oxide) ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and gardner.inv. reoxidize near6 nitrogen					
- 6 ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near3 oxide) ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and gardner.inv. - 23 reoxidize near6 nitrogen - 99 ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM (RTO "rapid thermal oxidation") near5 minute - 2 (RTO "rapid thermal oxidation") near5 minute - 2 (Tunnel oxide".clm.	'				
(oxygen or "0.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near3 oxide)		_		IICDAM.	2002/04/28
pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near3 oxide) ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and gardner.inv. reoxidize near6 nitrogen USPAT; 2003/04/28 EPO; JPO 12:56 USPAT; 2003/04/28 EPO; JPO 12:56 USPAT; 2003/04/28 EPO; JPO 13:28 ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM (RTO "rapid thermal oxidation") near5 minute "tunnel oxide".clm. USPAT; 2003/04/28 EPO; JPO 13:28 USPAT; 2003/04/28 EPO; JPO 13:28 USPAT; 2003/04/28 EPO; JPO 13:28 USPAT; 2003/04/28	-	•			
near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near3 oxide) ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and gardner.inv. 23 reoxidize near6 nitrogen ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM (RTO "rapid thermal oxidation") near5 minute (690 "tunnel oxide".clm. "USPAT; 2003/04/28 EPO; JPO 13:28 USPAT; 2003/04/28 EPO; JPO 13:28				EFO, OFO	12.40
anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and (ultrathin near3 oxide) ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and gardner.inv. reoxidize near6 nitrogen - 99 ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM (RTO "rapid thermal oxidation") near5 minute - 10					
"N.sub.4") Si3N4 nitride)) and (ultrathin near3 oxide) (((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and gardner.inv. 23 reoxidize near6 nitrogen 99 ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM - 2 (RTO "rapid thermal oxidation") near5 minute "tunnel oxide".clm. "USPAT; 2003/04/28 EPO; JPO 13:28 EPO; JPO 13:28 EPO; JPO 13:28 USPAT; 2003/04/28 EPO; JPO 13:28					
- 26 ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and gardner.inv. - 23 reoxidize near6 nitrogen 99 ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM - 2 (RTO "rapid thermal oxidation") near5 minute - 690 "tunnel oxide".clm. USPAT; 2003/04/28 EPO; JPO 13:28 EPO; JPO 13:28 USPAT; 2003/04/28 EPO; JPO 13:28					
(oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and gardner.inv. 23 reoxidize near6 nitrogen 99 ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM 10	1				
pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and gardner.inv. 23 reoxidize near6 nitrogen 99 ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM 10 (RTO "rapid thermal oxidation") near5 minute 11 minute 12 minute 13 minute 14 minute 15 minute 16 minute 16 minute 17 minute 18 minute 19 minute 10 minute 20 minute 21 minute 22 minute 23 minute 24 minute 25 minute 26 minute 27 minute 28 minute 29 minute 20 minut	-	26			1 ' ' 1
near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and gardner.inv. 23 reoxidize near6 nitrogen USPAT; 2003/04/28 EPO; JPO 12:56 USPAT; 2003/04/28 EPO; JPO 12:56 USPAT; 2003/04/28 EPO; JPO 13:28 SPO; JPO 13:28 Pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM RTO "rapid thermal oxidation") near5 minute (RTO "rapid thermal oxidation") near5 minute Tunnel oxide".clm. PART; 2003/04/28 EPO; JPO 13:28 USPAT; 2003/04/28 EPO; JPO 13:28				EPO; JPO	12:55
anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and gardner.inv. 23 reoxidize near6 nitrogen USPAT; 2003/04/28 EPO; JPO 12:56 USPAT; 2003/04/28 EPO; JPO 12:56 USPAT; 2003/04/28 EPO; JPO 13:28 PO; JPO 13:28					
"N. sub.4") Si3N4 nitride)) and gardner.inv. - 23 reoxidize near6 nitrogen USPAT; 2003/04/28 EPO; JPO 12:56 USPAT; 2003/04/28 EPO; JPO 12:56 USPAT; 2003/04/28 EPO; JPO 13:28 USPAT; 2003/04/28 EPO; JPO 13:28 IN. sub.4") Si3N4 nitride)) and EEPROM - 2 (RTO "rapid thermal oxidation") near5 minute minute - 690 "tunnel oxide".clm. USPAT; 2003/04/28 EPO; JPO 13:28 USPAT; 2003/04/28 EPO; JPO 13:28					
gardner.inv.					
- 23 reoxidize near6 nitrogen - 99 ((((hydrogen or "H.Sub.2") near "3"					
- 99 ((((hydrogen or "H.Sub.2") near "3" (oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM - 2 (RTO "rapid thermal oxidation") near5 minute - 690 "tunnel oxide".clm. EPO; JPO USPAT; 2003/04/28 EPO; JPO 13:28	_	23		USPAT;	2003/04/28
(oxygen or "O.sub.2")) or (pyrogenic pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM (RTO "rapid thermal oxidation") near5 minute - 690 "tunnel oxide".clm. EPO; JPO 13:28 EPO; JPO 13:28 USPAT; 2003/04/28 EPO; JPO 13:28				EPO; JPO	12:56
pyrogenically pyrogenical wet steam)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM (RTO "rapid thermal oxidation") near5 minute minute 690 "tunnel oxide".clm. USPAT; 2003/04/28 EPO; JPO 13:28 USPAT; 2004/02/26	-	99			
near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM (RTO "rapid thermal oxidation") near5 minute minute feo "tunnel oxide".clm. Near12 (oxidiz\$3 oxidation uspat; EPO; JPO 13:28 USPAT; 2004/02/26				EPO; JPO	13:28
anneal\$4 RTO) near12 (SiN("Si.sub.3" adj "N.sub.4") Si3N4 nitride)) and EEPROM (RTO "rapid thermal oxidation") near5 USPAT; 2003/04/28 minute minute EPO; JPO 13:28 Tunnel oxide".clm. USPAT; 2004/02/26					
"N.sub.4") Si3N4 nitride)) and EEPROM					
- 2 (RTO "rapid thermal oxidation") near5 USPAT; 2003/04/28 minute EPO; JPO 13:28 USPAT; 2004/02/26					
minute EPO; JPO 13:28	_	2		USPAT:	2003/04/28
- 690 "tunnel oxide".clm. USPAT; 2004/02/26			1 ' · · · · · · · · · · · · · · · · · ·		I I
	-	690			
				EPO; JPO	13:45